

L Number	Hits	Search Text	DB	Time stamp
8	19531	((356/399,400,401) or (355/53,55,69,70,71) or (250/548) or (430/5,20,22,30,311)).CCLS.	USPAT; US-PGPUB; EPO; JPO	2003/04/02 12:17
9	1825	((356/399,400,401) or (355/53,55,69,70,71) or (250/548) or (430/5,20,22,30,311)).CCLS.) and resistance	USPAT; US-PGPUB; EPO; JPO	2003/04/02 12:17
10	799	((356/399,400,401) or (355/53,55,69,70,71) or (250/548) or (430/5,20,22,30,311)).CCLS.) and resistance) and electrical\$2	USPAT; US-PGPUB; EPO; JPO	2003/04/02 12:17
11	506	((356/399,400,401) or (355/53,55,69,70,71) or (250/548) or (430/5,20,22,30,311)).CCLS.) and resistance) and electrical\$2) and mask	USPAT; US-PGPUB; EPO; JPO	2003/04/02 12:17
12	55	((356/399,400,401) or (355/53,55,69,70,71) or (250/548) or (430/5,20,22,30,311)).CCLS.) and resistance) and electrical\$2) and mask) and ((dose exposure) same (focus defocus))	USPAT	2003/04/02 12:18
-	283382	356/\$.ccls. 355/\$.ccls. 250/\$.ccls. 359/\$.ccls.	USPAT; US-PGPUB; EPO; JPO	2003/03/31 13:58
-	68034	(356/\$.ccls. 355/\$.ccls. 250/\$.ccls. 359/\$.ccls.) and (mask reticle target wafer substrate)	USPAT; US-PGPUB; EPO; JPO	2003/03/31 13:57
-	157	((356/\$.ccls. 355/\$.ccls. 250/\$.ccls. 359/\$.ccls.) and (mask reticle target wafer substrate)) and (dose same focus)	USPAT; US-PGPUB; EPO; JPO	2003/03/31 13:57
-	32	(356/\$.ccls. 355/\$.ccls. 250/\$.ccls. 359/\$.ccls. 430/\$.ccls. ) and (dose with sensitiv\$5) and (focus with sensitiv\$5)	USPAT; US-PGPUB; EPO; JPO	2003/03/31 14:18
-	193	((356/399,400,401) or (355/53,55,69,70,71) or (250/548) or (430/5,20,22,30,311)).CCLS.) and (dose same focus)) and (mask reticle target substrate wafer)	USPAT; US-PGPUB; EPO; JPO	2003/03/31 17:15
-	85	((356/399,400,401) or (355/53,55,69,70,71) or (250/548) or (430/5,20,22,30,311)).CCLS.) and (dose same focus)) and (resolv\$5 unresolv\$5)	USPAT; US-PGPUB; EPO; JPO	2003/03/31 19:01
-	132	((356/\$.ccls. 355/\$.ccls. 250/\$.ccls. 359/\$.ccls. 430/\$.ccls. ) and (mask reticle target wafer substrate)) and ((focus defocus) same (dose exposure intensity)) same (length width size))) and metrology	USPAT; US-PGPUB; EPO; JPO	2003/04/01 15:22
-	36	((356/\$.ccls. 355/\$.ccls. 250/\$.ccls. 359/\$.ccls. 430/\$.ccls. ) and (mask reticle target wafer substrate)) and ((focus defocus) same (dose exposure intensity)) same (length width size))) and metrology) and (resolv\$3 unresolv\$3)) and ((focus defocus) same (dose exposure intensity)) same sensitiv\$5)	USPAT; US-PGPUB; EPO; JPO	2003/04/01 15:29